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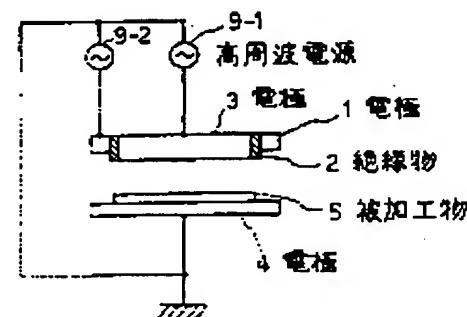
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(54) PLASMA TREATMENT APPARATUS

(57) Abstract:

PURPOSE: To start discharge readily at a low voltage and to prevent damages on a material to be machined, by providing a part, by which an interval between electrodes is made different, at a part of a facing electrode.

CONSTITUTION: With respect to an electrode 4, on which a material to be machined 5 is mounted, a facing electrode is divided into an electrode 1 and an electrode 3. The interval between the electrode 1 and the electrode 4 is set to be larger than the interval between the electrode 3 and the electrode 4. A specified gas is introduced in a treating tank 6. Then high frequency powers are applied to the electrodes 1 and 3 from high frequency power sources 9-1 and 9-2. When the electrode interval of 1cm or more is kept, the discharge is started readily. Therefore, the interval between the electrode 1 for starting the discharge and the electrode 4 is kept at 1cm or more. In this constitution, at first, the discharge is generated between the discharge starting electrode 1 and the electrode 4. Then, the discharge is induced and generated between the electrodes 3 and 4. Then, the high frequency power, which is supplied between the electrodes 1 and 4, is quickly turned OFF. Thus, the stable discharge is kept between the electrodes 3 and 4, and the material to be machined 5 can undergo, e.g., etching treatment.



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